

ABSTRACT

In an electron beam irradiation device comprising: an electron beam generating unit R, an irradiation chamber E for irradiating an electron beam to a irradiated object F, and an oxygen cutoff section S for blowing inert gas N on an upstream side of the irradiated chamber, the oxygen cutoff section is designed so that a gap W_s between partitions across the irradiated object is smaller than a gap W_e between the partitions across the irradiated object in the irradiation chamber ($W_s < W_e$), the gap W_s is made uniform or almost uniform throughout the entire area of the oxygen cutoff section, and a blowing slit S5 for blowing the inert gas to the processing surface of the irradiated object is provided on a partition with no projection nor recess involved.